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Microscale Processing with Non-thermal Plasma Discharges and Its Application

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Message from the Guest Editors

This Special Issue showcases cutting-edge examples of surface processing for use in applications within the fields of energy, biomedicine, and microelectronics. Non-equilibrium plasmas constitute very effective media of transport and delivery, having many purposes, such as coating deposition, surface etching/texturing, or functionalization. The scope here goes beyond the typical cases in the thin-film industry and aims to collect the latest know-how on the topics of (1) chemical modification for catalysis, biosensing, and microfluidics applications, and (2) surface engineering to manufacture or modify materials, including nano- and biomaterials.

The presented plasma techniques target processes in the domains of atoms, molecules, cells, and organic tissues. This Special Issue thereby welcomes contributions on plasma processes that seek to generate functional interfaces from the nano- to macroscale. Such a multiscale approach may enable the development of a multidisciplinary line of work aligned with some of the most relevant challenges in electronics, biology, and environmental engineering.

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Message from the Editor-in-Chief

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